

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#10 Kcooper 12-3-03

In re patent application of

Applicant:

Yoshimasa KAWASE

Title:

WAFER HEAT-TREATMENT SYSTEM AND WAFER HEAT-

TREATMENT METHOD

Appl. No.:

10/066,783

Filing Date:

February 6, 2002

Examiner:

G. Wilson

Art Unit:

3749

## **REPLY UNDER 37 C.F.R. § 1.111**

Mail Stop NON-FEE AMENDMENT Commissioner for Patents PO Box 1450 Alexandria, Virginia 22313-1450

Sir:

This communication is responsive to the Non-Final Office Action dated April 8, 2003, concerning the above-referenced patent application.

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